

New- Best in class media consumption for cutting-edge inline texturing and junction isolation

RENA's InTex® and InOxSide® systems on the NIAK platform

- **Best in class media consumption: Saving potential 4,200,000 €p.a. for a 1 GW fab.**
- **RENA is the only tool supplier granting texture license to all InTex® texturing machines**

Gütenbach, September 5th, 2011. One of the driving cost factors for wet chemical processing is media consumption. Optimised media handling and fluid dynamics in the NIAK inline tools InTex® and InOxSide® led to best in class media consumption. In both inline applications only 270 ml DI-water per wafer are necessary for rinsing operations. The acid usage per wafer in the InTex® texturing application is only 8.5 ml/wafer and for the junction isolation in the InOxSide solely 1.1 ml/wafer. This represents a saving potential of 4,200,000 € per year in a 1 GW fab compared to state of the art equipment.

RENA is the only equipment manufacturer providing a process and sales license for inline texturing in its InTex® and a patented single side etching process for the junction isolation in its InOxSide® tools. Thus RENA ensures that its customers comply with the legal requirements when distributing their products in the main cell and module markets EU and US.

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